



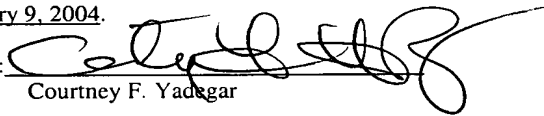
PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of:	)	
	)	Docket No. LAM2P295
Wen-Ben CHOU et al.	)	
	)	Examiner: Chen, Kin Chan
Application No. 09/998,858	)	
	)	Group Art Unit: 1765
Filed: October 31, 2001	)	
	)	Date: February 9, 2003
For: METHOD AND APPARATUS	)	
FOR NITRIDE SPACER ETCH	)	
PROCESS IMPLEMENTING -	)	
IN SITU INTERFEROMETRY	)	
ENDPOINT DETECTION AND	)	
NON-INTERFEROMETRY	)	
ENDPOINT MONITORING	)	

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail addressed to: Commissioner for Patents, P.O. Box 1450 Alexandria, VA 22313-1450 on February 9, 2004.

Signed:   
Courtney F. Yadegar

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

AMENDMENT

Dear Sir:

This is in response to the Final Office Action mailed on October 8, 2003 and the Advisory Action mailed on December 30, 2003. The period for response extends to February 9, 2004, with a one-month extension of time. Please enter the following amendments and remarks in the above-identified patent application:

Amendments to the claims are reflected in the Listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 10 of this paper.